



FORM PTO 449 (Modified)	Attorney Docket No.: 14089-002540US	Application No.: 09/165,513
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)	Applicant: VEERASAMY VIJAYEN et al.	
	Filing Date: October 2, 1998	Group:

Reference Designation		U.S. PATENT DOCUMENTS				Page 1
Examiner Initial	Document No.	Date	Name	Class	Sub-class	Filing Date (If Appropriate)
<u>SA</u> AA	4,123,316	10/31/78	Tsuchimoto	156	643	10/06/76
<u>SA</u> AB	4,226,666	10/07/80	Winters et al.	156	643	08/21/78
<u>SA</u> AC	4,822,466	04/18/89	Rabalais et al.	204	192.15	06/25/87
<u>SA</u> AD	5,017,835	05/21/91	Oechsner	315	111.81	11/20/89
<u>SA</u> AE	5,064,809	11/12/91	Hed	505	1	12/23/98
<u>SA</u> AF	5,082,359	01/21/92	Kirkpatrick	359	642	11/28/89
<u>SA</u> AG	5,082,522	01/21/92	Purdes et al.	156	612	08/14/90
<u>SA</u> AH	5,091,049	02/25/92	Campbell et al.	156	643	06/29/90
<u>SA</u> AI	5,126,206	06/30/92	Garg et al.	428	408	09/06/90
<u>SA</u> AJ	5,156,703	10/20/92	Oechsner	156	643	11/20/89
<u>SA</u> AK	5,182,132	01/26/93	Murai et al.	427	577	12/03/90
<u>SA</u> AL	5,186,973	02/16/93	Garg et al.	427	590	09/13/90
<u>SA</u> AM	5,246,884	09/21/93	Jaso et al.	437	225	10/30/91
<u>SA</u> AN	5,374,318	12/20/94	Rabalais et al.	148	33	02/24/89
<u>SA</u> AO	5,423,915	06/13/95	Murata et al.	118	723	09/28/93
<u>SA</u> AP	5,462,784	10/31/95	Grill et al.	428	65.5	11/02/94
<u>SA</u> AQ	5,466,431	11/14/95	Dorfman et al.	423	446	05/25/94
<u>SA</u> AR	5,559,367	09/24/96	Cohen et al.	257	77	07/12/94

FOREIGN PATENT DOCUMENTS						
	Document No.	Date	Country	Class	Sub-class	Translation (Yes/No)
<u>SA</u> AS ✓	02168540	06/28/90	Japan	H01J	27/18	Yes
<u>SA</u> AT	5-143971	06/11/93	Japan	G11B	5/72	No
<u>SA</u> AU	0 552 491 A1	07/28/93	Europe	H01J	37/32	Yes
<u>SA</u> AV	0 595 564 A2	05/04/94	Europe	G11B	5/72	Yes
<u>SA</u> AW	6-199560	05/20/94	Japan	G11B	5/72	No
<u>SA</u> AX ✓	06349054	12/22/94	Japan	G11B	5/72	Yes
<u>SA</u> AY	EP 0 700 033 A2	03/06/96	Europe	G11B	5/31	Yes

EXAMINER <u>[Signature]</u>	DATE CONSIDERED <u>11-10-2000</u>
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO-1449 (Modified)		Attorney Docket No.: 14089-002540US	Application No.: 09/165,513
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		Filing Date: October 2, 1998	Group:
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)			
<u>BA</u> AZ ✓	Boxman, R.L. et al. "Recent Progress in Filtered Vacuum Arc Deposition," <i>Paper submitted, Int. Conf. Metallurgical Coatings and Thin Films, San Diego, April 1996.</i>		
<u>BA</u> BA ✓	Veerasamy, V.S. et al. "Electronic Density of States in Highly Tetrahedral Amorphous Carbon," <i>Solid-State Electronics</i> , Vol. 37, No. 2, pp. 319-326, 1994.		
<u>BA</u> BB ✓	Weiler, M. et al. "Preparation and Properties of Highly Tetrahedral Hydrogenated Amorphous Carbon," <i>Physical Review B</i> , Vol. 53, No. 3, pp. 1594-1608, 1996.		
<u>BA</u> BC ✓	Weiler, M. et al. "Structure of Amorphous Hydrogenated Carbon: Experiment and Computer Simulation," <i>Diamond and Related Materials</i> , Vol. 3, pp. 245-253, 1994.		
<u>BA</u> BD ✓	Chhowalla, M. et al. "Deposition of Smooth Tetrahedral Amorphous Carbon Thin Films Using a Cathodic Arc Without a Macroparticle Filter," <i>Appl. Phys. Lett.</i> , Vol. 67, No. 7, pp. 894-896, 1995.		
<u>BA</u> BE ✓	Chhowalla, M. et al. "Stationary Carbon Cathodic Arc: Plasma and Film Characterization," <i>J. Appl. Phys.</i> , Vol. 79, No. 5, pp. 2237-2244, 1996.		
<u>BA</u> BF ✓	Oechsner, H. "Electron Cyclotron Wave Resonances and Power Absorption Effects in Electrodeless Low Pressure H.F. Plasmas with a Superimposed Static Magnetic Field," <i>Plasma Physics</i> , Vol. 16, pp. 835-844, 1974.		
<u>BA</u> BG ✓	Oechsner, H. et al. "An RF Plasma Beam Source for Thin Film and Surface Technology," <i>Proc. 1st Int. Conf. on Plasma Surface Engineering, Garmisch Partenkirchen</i> , 1988, Vol. II, DGM Informationen Gesellschaft, Obvuroel, pp. 1017-1024, 1989.		
<u>BA</u> BH ✓	Pfeiffer, B. "Skin Effect in Anisotropic Plasmas and Resonance Excitation of Electron-Cyclotron Waves. I. Theory," <i>Journal of Applied Physics</i> , Vol. 37, No. 4, pp. 1624-1627, 1966.		
<u>BA</u> BI ✓	Sager, O. "The Influence of Nonuniform Density Distribution and Electron Temperature on the Helicon-Resonances in Low Pressure Discharges," 1971.		
<u>BA</u> BJ ✓	Szuszczewicz, Edward P., "Spatial Distributions of Plasma Density in a High-Frequency Discharge with a Superimposed Static Magnetic Field," <i>The Physics of Fluids</i> , Vol. 15, No. 12, pp. 2240-2246, 1972.		
<u>BA</u> BK ✓	Weiler, M. et al. "Highly Tetrahedral, Diamond-like Amorphous Hydrogenated Carbon Prepared from a Plasma Beam Source," <i>Appl. Phys. Lett.</i> , Vol. 64, No. 23, pp. 2797-2799, 1994.		
<u>BA</u> BL ✓	Kühn, M., et al. "Deposition of Carbon Films By A Filtered Cathodic Arc," <i>Diamond and Related Materials</i> , Vol. 2, No. 10, August 1993, pp. 1350-1354.		
<u>BA</u> BM ✓	Grill, A., et al. "Diamondlike Carbon Films by rf Plasma-Assisted Chemical Vapor Deposition from Acetylene," <i>IBM J. Res. Develop.</i> , Vol. 34, No. 6, November 1990, pp. 849-857		
<u>BA</u> BN ✓	Aisenberg, S., et al. "Ion-Beam Deposition of Thin Films of Diamondlike Carbon," <i>J. Appl. Phys.</i> , Vol. 42, No. 7, June 1971, pp. 2953-2958		
<u>BA</u> BO ✓	Grill, A., et al. "Diamondlike Carbon Deposited by DC PACVD," <i>Diamond Films and Techn.</i> , Vol. 1, No. 4, (1992), pp. 219-233.		
BA BP ✓	Thesis by Manfred Weiler, 1989.		
BA BQ ✓	Dissertation by Manfred Weiler, 1994.		
BA BR ✓	Dissertation by Dieter Martin, 1995.		
BA BS ✓	Thesis by Franz Schön, 1968.		
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